

TRADEMARK ASSIGNMENT

Electronic Version v1.1
 Stylesheet Version v1.1

SUBMISSION TYPE:	NEW ASSIGNMENT
NATURE OF CONVEYANCE:	SECURITY INTEREST

CONVEYING PARTY DATA

Name	Formerly	Execution Date	Entity Type
RAVE N.P., INC.		09/01/2011	CORPORATION: DELAWARE

RECEIVING PARTY DATA

Name:	BRIDGE BANK, NATIONAL ASSOCIATION
Street Address:	55 ALMADEN BOULEVARD, SUITE 100
City:	SAN JOSE
State/Country:	CALIFORNIA
Postal Code:	95113
Entity Type:	NATIONAL ASSOCIATION: UNITED STATES

PROPERTY NUMBERS Total: 9

Property Type	Number	Word Mark
Registration Number:	3786068	NANOSNOW
Registration Number:	3923748	SNOWSTRIP
Registration Number:	2429388	ECO-SNOW
Registration Number:	2436017	WAFERCLEAN
Registration Number:	3434792	WAFERCLEAN
Registration Number:	3316127	VERSACLEAN
Registration Number:	3316126	MASKCLEAN
Registration Number:	3070328	PRECISIONCLEAN
Registration Number:	3316697	PRECISIONCLEAN

CORRESPONDENCE DATA

Fax Number: (858)638-5016
Correspondence will be sent via US Mail when the fax attempt is unsuccessful.
 Phone: 8586771416
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 Correspondent Name: DLA PIPER LLP (US)

900201200

TRADEMARK
REEL: 004615 FRAME: 0282

CH \$240.00 3786068

Address Line 1: ATTN: LISA ORTIZ
Address Line 2: 4365 EXECUTIVE DRIVE, SUITE 1100
Address Line 4: SAN DIEGO, CALIFORNIA 92121

ATTORNEY DOCKET NUMBER:	355157-000102
NAME OF SUBMITTER:	TROY ZANDER
Signature:	/S/ TROY ZANDER
Date:	09/01/2011

Total Attachments: 5
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INTELLECTUAL PROPERTY SECURITY AGREEMENT

This INTELLECTUAL PROPERTY SECURITY AGREEMENT, dated as of «Date»September 1, 2011 (the "Agreement") between BRIDGE BANK, NATIONAL ASSOCIATION ("Lender") and RAVE N.P., INC.«Borrower». ("Grantor") is made with reference to the Business Financing Agreement, dated as of September 1, 2011 (as amended from time to time, the "Financing Agreement"), by and among Lender, Grantor and RAVE, LLC. Terms defined in the Financing Agreement have the same meaning when used in this Agreement.

For good and valuable consideration, receipt of which is hereby acknowledged, Grantor hereby covenants and agrees as follows:

To secure the Obligations under the Financing Agreement, Grantor grants to Lender a security interest in all right, title, and interest of Grantor in any of the following, whether now existing or hereafter acquired or created in any and all of the following property (collectively, the "Intellectual Property Collateral"):

(a) copyright rights, copyright applications, copyright registrations and like protections in each work or authorship and derivative work thereof, whether published or unpublished and whether or not the same also constitutes a trade secret, now or hereafter existing, created, acquired or held (collectively, the "Copyrights"), including the Copyrights described in Exhibit A;

(b) trademark and servicemark rights, whether registered or not, applications to register and registrations of the same and like protections, and the entire goodwill of the business of Borrower connected with and symbolized by such trademarks (collectively, the "Trademarks"), including the Trademarks described in Exhibit B;

(c) patents, patent applications and like protections including without limitation improvements, divisions, continuations, renewals, reissues, extensions and continuations-in-part of the same (collectively, the "Patents"), including the Patents described in Exhibit C;

(d) mask work or similar rights available for the protection of semiconductor chips or other products (collectively, the "Mask Works");

(e) trade secrets, and any and all intellectual property rights in computer software and computer software products;

(f) design rights;

(g) claims for damages by way of past, present and future infringement of any of the rights included above, with the right, but not the obligation, to sue for and collect such damages for said use or infringement of the intellectual property rights identified above;

(h) licenses or other rights to use any of the Copyrights, Patents, Trademarks, or Mask Works, and all license fees and royalties arising from such use to the extent permitted by such license or rights;

(i) amendments, renewals and extensions of any of the Copyrights, Trademarks, Patents, or Mask Works; and

(j) proceeds and products of the foregoing, including without limitation all payments under insurance or any indemnity or warranty payable in respect of any of the foregoing.

The rights and remedies of Lender with respect to the security interests granted hereunder are in addition to those set forth in the Financing Agreement, and those which are now or hereafter available to Lender as a matter of law or equity. Each right, power and remedy of Lender provided for herein or in the Financing

Agreement, or now or hereafter existing at law or in equity shall be cumulative and concurrent and shall be in addition to every right, power or remedy provided for herein, and the exercise by Lender of any one or more of such rights, powers or remedies does not preclude the simultaneous or later exercise by Lender of any other rights, powers or remedies.

IN WITNESS WHEREOF, the parties have executed this Agreement as of the date first written above.

GRANTOR:

RAVE, N.P., INC.

By: *Billy Hopkins*

Name: *Billy Hopkins*

Title: *PRESIDENT & CEO*

LENDER:

BRIDGE BANK, NATIONAL ASSOCIATION

By: *Jeffrey Javier*

Name: *JEFFREY JAVIER*

Title: *SVP*

Address for Notices:

Attn:
4935A Southfront Road
Livermore, CA 94551
Fax:

Address for Notices:

Attn: Note Department
55 Almaden Boulevard, Suite 100
San Jose, California 95113
Tel: (408) 556-6501
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RAVE N.P., Inc. Registered Copyrights

Tab	Matter	Country	Work	Status	App #	Filing Date	Reg. Number	Reg. Date	Legal Owner	Recorded Owner
	20001	US	Maskclean 150 Software	Pending		02/07/10			RAVE N.P., Inc.	RAVE, N.P., Inc.
		US	Waferclean 1600 Software	Registered			TX5-954-215		RAVE N.P., Inc.	RAVE, N.P., Inc.
		US	Waferclean 1600 Software	Registered			TX5-903-905		RAVE N.P., Inc.	RAVE, N.P., Inc.

Matter	Country	Trademark	Status	App #	Filing Date	Reg. Number	Reg. Date	Class	Recorded Owner
	US	NANOSNOW	Registered		05/20/09	3,786,068	05/04/10		RAVE, N.P., Inc.
20000	US	SNOWSTRIP	Registered	77741212	05/20/09	3,923,748	02/22/11	3	RAVE N.P., Inc.
20004	US	ECO-SNOW	Registered	75751354	07/14/99	2,429,388	02/20/01	03	RAVE, N.P., Inc.
	JP	ECO-SNOW	Registered			4,902,470			RAVE, N.P., Inc.
20006	CH	ECO-SNOW	Registered			6,794,550		07	RAVE, N.P., Inc.
0018	US	WAFERCLEAN	Registered	75751353	07/14/99	2,436,017	03/13/01		RAVE, N.P., Inc.
	US	WAFERCLEAN	Registered	777271136	09/04/07	3,434,792	05/27/08		RAVE, N.P., Inc.
	JP	WAFERCLEAN	Registered			4,904,954			RAVE, N.P., Inc.
	US	VersaClean	Registered	777076999	01/05/07	3,316,127	10/23/07		RAVE, N.P., Inc.
	JP	VersaClean	Registered			4,902,472			RAVE, N.P., Inc.
	US	MaskClean	Registered	777076955	01/05/07	3,316,126	10/23/07		RAVE, N.P., Inc.
	JP	MaskClean	Registered			4,902,472			RAVE, N.P., Inc.
20014	US	PrecisionClean	Registered	78479254	09/07/04	3,070,328	03/21/06		RAVE, N.P., Inc.
	US	PrecisionClean	Registered	777102673	02/08/07	3,316,697	10/23/07		RAVE, N.P., Inc.
	JP	PrecisionClean	Registered			5,090,000			RAVE, N.P., Inc.

Pub. No.	Name	Country	Pub. No.	Pub. Date	Pub. No.	Pub. Date	Status
RAVE NP, Inc. Patents and Patent Applications							13 pending; 67 issued; 2 abandoned
21501	Fluid Injection Assembly for Nozzles	U.S.	12808,750	Filed 01/17/10, filing date 7/13/11			Filed response to missing parts 7/11. Pending
21502	Fluid Injection Assembly for Nozzles	Japan	pending	Filed 02/20/10			Request exam or lapse by 11/15/11. Asked BH to pursue based on Bowers advice 7-28-11.
21503	Fluid Injection Assembly for Nozzles	Taiwan	067149944	Filed 12/12/08			Request exam or lapse by 11/15/11. Asked BH to pursue based on Bowers advice 7-28-11.
21504	Fluid Injection Assembly for Nozzles	KR	10-2010-7018281				Not part of original deal docs. Pending
21520	Post-CMP cleaning of semiconductor wafer surfaces using a combination of aqueous and CO2 based cryogenic cleaning	EP	03706,394.5	Filed 1/29/03			Final OA rec'd 3/31/11. Response due 7/6/11 (extended to 8/6). No. were marked commercial - removed with "other call 9-3-11". Action in dispute re: response
21540	CO2 Nozzles	U.S.	12,559,643	Filed 01/30/09			pending
21541	CO2 Nozzles	PCT	US10/48032				Not part of original deal docs. Pending
21542	CO2 Nozzles	TVY	86130241	Filed 10/1/10			Not part of original deal docs. Pending
21560	CO2 system for polymer film cleaning	U.S.	12,281,157	Filed 10/30/08			OA rec'd 11/10. Response filed 1/11. Final OA rec'd 4/11. IP team agreed prior art not worth fighting further. Instructed BH to abandon 7-28-11. Expired 8-5-11.
21580	Method for selective metal film layer removal using CO jet spray	Canada	2422082	Filed 01/20/11	2,422,082		Abandoned 3-2-11; CB confirmed prior art is sufficient & owned by RAVE
21600	Environment Control Apparatus	U.S.	06/033,808		5,316,590		issued 5/31/94
21620	System for Precision cleaning by Jet spray	U.S.	07773,884		5,315,763		issued 5/31/94
21621	System for Precision cleaning by Jet spray	Canada	2,077,485		2,077,483		issued 4/23/99
21622	System for Precision cleaning by Jet spray	Japan	2638592		2,785,787		issued 4/23/98
21623	System for Precision cleaning by Jet spray	EP	02114942.4		525580		Not part of original deal docs
21624	System for Precision cleaning by Jet spray	Germany	02116348.4		339630		issued 4/17/96
21625	System for Precision cleaning by Jet spray	France	02116848.4		339630		issued 4/17/96
21626	System for Precision cleaning by Jet spray	UK	02116848.4		035680		issued 4/17/96
21842	System for cleaning a surface using Cryogenic Aerosol and fluid reactant	U.S.	11/739,847	Filed 01/10/07			Abandoned 3-2-11; CB confirmed prior art is sufficient & owned by RAVE
21843	System for cleaning a surface using Cryogenic Aerosol and fluid reactant	Malaysia	P120051745	Filed 4/20/05			pending
21844	System for cleaning a surface using Cryogenic Aerosol and fluid reactant	Thailand	098711	Filed 4/20/05			pending
21845	System for cleaning a surface using Cryogenic Aerosol and fluid reactant	Taiwan	094112810	Filed 4/20/05			pending
21860	Apparatus and method for cleaning large glass plates using linear arrays of CO2 jet spray nozzles	U.S.	09/727,809		5,836,809		issued 11/17/98
21860	Electrostatic discharge protection of static sensitive devices cleaned with CO2 spray	U.S.	08/821,890		5,837,084		issued 11/17/98
21700	CO2 jet spray nozzle with sensor apparatus for use with jet spray	U.S.	09/850,873		5,884,828		issued 9/8/98
21720	CO2 jet spray nozzle with multiple orifices	U.S.	09/157,094		6,173,916		issued 11/6/01
21721	CO2 Jet Spray Nozzles with Multiple Orifices	EP	05117717.9		721801		Not part of original deal docs
21722	CO2 Jet Spray Nozzles with Multiple Orifices	U.K.	05117717.9		721801		issued 6/2/99
21723	CO2 Jet Spray Nozzles with Multiple Orifices	France	05117717.9		721801		issued 6/2/99
21724	CO2 Jet Spray Nozzles with Multiple Orifices	Germany	05117717.9		721801		issued 6/2/99
21740	Modular CO2 jet spray device	U.S.	09/855,124		5,811,431		issued 9/18/97
21760	Optical sensing apparatus for CO2 jet spray	U.S.	09/403,038		5,961,527		issued 10/1/98
21761	Optical sensing apparatus for CO2 jet spray	EP	09100292.0		732150		Not part of original deal docs
21762	Optical sensing apparatus for CO2 jet spray	Germany	09100292.0		68017502 9-08		issued 12/5/01
21763	Optical sensing apparatus for CO2 jet spray	France	09100292.0		732150		issued 12/5/01
21764	Optical sensing apparatus for CO2 jet spray	U.K.	09100292.0		732150		issued 12/5/01
21780	Electrostatic discharge control during jet spray	U.S.	07/869,128		5,408,418		issued 4/26/96
21781	Electrostatic discharge control during jet spray	Canada	2,103,743		2,103,743		issued 11/5/95
21782	Electrostatic Discharge Control During the Removal of Contaminants from Surfaces by Means of a Jet Spray	EP	03115274.8		580495		Not part of original deal docs
21783	Electrostatic discharge control during jet spray	Germany	03115274.8		69310030 3-06		issued 5/14/97
21784	Electrostatic Discharge Control During the Removal of Contaminants from Surfaces by Means of a Jet Spray	France	03115274.8		580495		issued 5/14/97
21785	Electrostatic Discharge Control During the Removal of Contaminants from Surfaces by Means of a Jet Spray	U.K.	03115274.8		580495		issued 5/14/97
21786	Electrostatic Discharge Control During the Removal of Contaminants from Surfaces by Means of a Jet Spray	NL	03115274.8		580495		Not part of original deal docs
21800	Method for cleaning surface by heating and a stream of snow	U.S.	08/066,884		5,354,384		issued 10/11/94
21801	Dual Jet Spray Cleaner (incorrect on original deal docs as "Method for cleaning surface by heating and a stream of snow")	Canada	2,127,402		2,122,402		issued 10/6/98
21802	Dual Jet Spray Cleaner	EP	04100368.5		622129		Not part of original deal docs
21803	Dual Jet Spray Cleaner (incorrect on original deal docs as "Method for cleaning surface by heating and a stream of snow")	Germany	04100368.5		622129		issued 12/23/98
21804	Dual Jet Spray Cleaner (incorrect on original deal docs as "Method for cleaning surface by heating and a stream of snow")	France	04100368.5		622129		issued 12/23/98
21805	Dual Jet Spray Cleaner (incorrect on original deal docs as "Method for cleaning surface by heating and a stream of snow")	UK	04100368.5		622129		issued 12/23/98
21806	Dual Jet Spray Cleaner	NL	04100368.5		622129		Not part of original deal docs
21822	Liquid-assisted cryogenic cleaning	Singapore	200402815-6		105623		issued 10/31/06
21823	Liquid-assisted cryogenic cleaning	Taiwan	02113360		1,278927		issued 4/11/07
21842	Post-CMP cleaning of semiconductor wafer surfaces using a combination of aqueous and CO2 based cryogenic cleaning	China	03818420.1		1003/7696C (incorrect on original deal docs as "3818420.1")		issued 4/2/06
21843	Post-CMP cleaning of semiconductor wafer surfaces using a combination of aqueous and CO2 based cryogenic cleaning	Japan	2003-127189		378C-351		issued 3/31/06
21844	Post-CMP cleaning of semiconductor wafer surfaces using a combination of aqueous and CO2 based cryogenic cleaning	Singapore	200500638-5		110342		issued 1/31/07
21845	Post-CMP cleaning of semiconductor wafer surfaces using a combination of aqueous and CO2 based cryogenic cleaning	Taiwan	02113367		1,248783		issued 2/21/06
21851	Liquid-assisted cryogenic cleaning	U.S.	10/324,221		6,852,173		issued 2/6/06
21862	Liquid-assisted cryogenic cleaning	U.S.	10/633,251		7,056,391		issued 6/6/06
21831	Vapor-assisted cryogenic cleaning	U.S.	10/408,147		6,949,145		issued 8/27/05
21900	Method for selective metal film layer removal using CO jet spray	U.S.	09/850,354		6,500,758		issued 12/31/02
21902	Method for selective metal film layer removal using CO jet spray	China	01819480.3		1615480.3		issued 4/23/07
21903	Method for selective metal film layer removal using CO jet spray	Japan	2002-627584		4008533		issued 9/7/07
21904	Method for selective metal film layer removal using CO jet spray	Taiwan	80122819		172759		issued 6/25/03
21905	Method for selective metal film layer removal using CO jet spray	Singapore	200301140-0		85341		issued 10/31/05
21906	Method for selective metal film layer removal using CO jet spray	EP	01870633.2		1317767		Not part of original deal docs
21906	Method for selective metal film layer removal using CO jet spray	Germany	01870633.2		EP1317767		issued 2/21/07
21908	Method for selective metal film layer removal using CO jet spray	France	01870633.2		EP1317767		issued 2/21/07
21910	Method for selective metal film layer removal using CO jet spray	UK	01870633.2		EP1317767		issued 2/21/07
21911	Method for selective metal film layer removal using CO jet spray	Ireland	01870633.2		EP1317767		issued 2/21/07
21912	Method for selective metal film layer removal using CO jet spray	Italy	01870633.2		EP1317767		issued 2/21/07
21913	Method for selective metal film layer removal using CO jet spray	Netherlands	01870633.2		EP1317767		issued 2/21/07
21920	Apparatus for cleaning and testing wafer components of hard drives and the like	U.S.	08/905,610		5,969,355		issued 11/23/99
21940	Use of electrostatic bias to clean non-electrostatically sensitive components with a carbon dioxide spray	U.S.	08/816,854		5,148,486		issued 11/14/00
21960	Integrated circuit chip module cleaning using CO2 jet spray	U.S.	08/813,287		5,736,568		issued 6/16/98
21960	Photorealist and redeposition removal using CO2 jet spray	U.S.	08/814,792		5,853,962		issued 1/23/98
22000	CO2 jet spray disk cleaning system	U.S.	08/789,897		5,836,544		issued 9/15/98
22020	CO2 jet spray park cleaning system (aka P31000 tool)	U.S.	08/816,522		5,053,389		issued 6/6/00
22040	Wafer coating using a lower end CO2 snow	U.S.	08/850,674		5,063,092		issued 5/23/00
22060	Apparatus and method for analysis of impurities in liquid CO2	U.S.	08/411,398		5,276,189		issued 8/21/01
22061	Apparatus for analysis of impurities in liquid CO2	U.S.	08/963,088		6,405,580		issued 6/16/01
22060	A Novel Integrated Cleaning Technique for Residual Defects Fluid Injection Assembly for Nozzles	US	Provisional App	Filed 11/03/10			Provisional App filed 11/3/10. Pending
		PCT	PCT/US08/08877	Filed 12/15/08			pending